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- .5 V

β-Ga₂O₃ for Next Generation X-ray Detectors

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Outline

- I. Motivation
- II. Introduction
- III. Optical and electrical characteristics of β -Ga₂O₃ (Fe)
- IV. X-ray Induced Current (XRIC) Characterization
- V. Temperature-dependent Cathodoluminescence (CL) for β -Ga₂O₃ (Fe)
- VI. Summary



I. Motivation – the need for (U)WBG detectors

- Radiation detectors are key components for numerous products and applications.
- Elementary detectors have many limitations related to their intrinsic material properties.
 - Harsh environment
 - Cooling and compromised density
 - High Voltage operation
- Wide and ultrawide bandgap semiconductors are much less susceptible to displacement damage by particle irradiation than elemental and narrow bandgap compound semiconductors.



. Motivation – Ga₂O₃ for radiation detection

- β-Ga₂O₃ has many material advantages
 - Thermal stability (M. P. > 1800 °C)
 - The least mature and most recent ultrawide bandgap material (4.5 5.1 eV)
 - Very high breakdown electric field (8 MV/m)
 - Control of n-type conductivity via doping and post-growth processes
 - High-quality bulk single crystals from melt
 - Cost-effective large-scale manufacturability
- β-Ga₂O₃ holds high promise for addressing many radiation detection application needs not met by currently used materials
 - Harsh environment applicability
 - Versatile and cost-effective synthesis and fabrication
 - High detector performance



J. Zhang et al., "Recent progress on the electronic structure, defect, and doping properties of Ga_2O_3 ," APL Materials, 8, 2, 20906, 2020.



II. Introduction – X-ray sensors based on β-Ga₂O₃

- One previous study published in 2018-2019
 - Annealed at 1500 °C in air atmosphere for 48 hours
 - Double-side chemical mechanical polishing (CMP)
- Response linearity was demonstrated with no saturation effect.
- High photo-to-dark current ratio exceeding 800 at –15 V.
- When biased at 0V, the detector showed perfect photovoltaic characteristics, demonstrating the great potential of using β-Ga₂O₃ SBDs as passive X-ray detectors or X-ray photocells.



II. Introduction – X-ray sensors based on β-Ga₂O₃

• Two different time constants are obtained for the photocurrent rising process ($\tau_{r1} = 13.8 \ s$ and $\tau_{r2} = 1.4 \ s$), while during the photocurrent decaying process the two time-constants are $\tau_{d1} = 17.1 \ s$ and $\tau_{d2} = 4.0 \ s$.

 The fast response of an unbiased SBD detector corresponds to a photovoltaic mechanism, where the photo-generated carriers in the space-charge region are swept out rapidly by the build-in electric filed.



X. Lu et al., "X-ray Detection Performance of Vertical Schottky Photodiodes Based on a Bulk β -Ga₂O₃ Substrate Grown by an EFG Method," ECS J. Solid State Sci. Technol. 8, 7, Q3046–Q3049, 2019.



III. Optical and electrical characterization – bandgap

- Optical bandgap deducted from Tauc plot was 4.45 eV based on direct band gap treatment.
- No near band-gap shoulder was shown.
- The UWB opens the path for UV detection and the possibility for x-ray, γ-ray detection as well as charged particles.

Wavelength (nm) 318 310 302 302 295 282 282 282 270 270 270 275 253 253 253 326 $(\alpha hv)^2$ 4x10⁵ 4x10⁵ Wavelength (nm) ទ្នុ ឆ្នំ ខ្ល 413 310 96 276 $(\alpha hv)^2$ (eV²cm⁻²) Absorbance (arb. units) - Absorbance 3x10⁵ • 3x10⁵ 2x10⁵ · 2x10^t 22 0.0 3.5 4.0 Photon Energy (eV) 1x10⁵ 1x10⁶ 3.5 .5 9.1 3.0 3.3 3.4 3.7 8.8 3.9 £.0 ÷ 2 ... 5 8. 6.1 0.0 Photon Energy (eV)

I. Hany et al., "Low temperature cathodoluminescence study of Fe-doped β -Ga₂O₃," Materials Letters 257, 126744, 2019.

11/04/2020

Tauc Plot showing optical bandgap of 4.45 eV. Inset shows optical absorption curve raw data which was used for Tauc plot construction.

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III. Optical and electrical characterization – resistivity

- 4x4 mm² Au/Ti (50/50 nm) electrodes were deposited on both sides of 5x5 mm² sample.
 - DC sputtering for Ti, e-beam for Au
- Very high resistivity in the order of $10^{14} \Omega$.cm was revealed from I-V measurement.
- 4x4 mm² Au/Ti (50/50 nm) and Au/Ni (40/50 nm) electrodes were deposited for testing Schottky behavior; however the I-V behavior was not different from the Au/Ti Ohmic sample.
 - DC sputtering for Ti, e-beam for Au and Ni
- Controlled 10-minute air annealing at 400 °C didn't change I-V behavior for both samples.



Au/Ni/ β -Ga_2O_3/Ti/Au and Au/Ti/ β -Ga_2O_3/Ti/Au



In-house built versatile testing box used for I-V, XRIC and UVIC measurements

Au/Ti/β-Ga₂O₃/Ti/Au I-V characteristic curve

I. Hany et al., "Low temperature cathodoluminescence study of Fe-doped β -Ga₂O₃," Materials Letters 257, 126744, 2019



- Zero Voltage mode (Passive operation) (45 KV, 40 mA)
 - X-ray induced current reaching -21 pA
 - Dark transient current of -0.15 (+/-0.05) pA
 - SNR = 139
 - No experimental lag

 $SNR = \frac{I_{x-ray \ induced} - I_{dark}}{I_{dark}}$

Idark







SNR

IV. XRIC Characterization

- SNR for operating voltages between -5 V and -50 V stays above 800 and decreases for the higher applied voltages.
- SNR stays above 1000 for applied voltages between -5 V and -20 V, and it is further optimized at -5 V exceeding 1200.
- μτ factor calculated from single carrier Hecht model treatment was 2.28x10⁻⁵ cm²/V
 - 45.6 µm carrier drift length for 10 V.
 - 456 µm carrier drift length for 100 V.



I. Hany et al., "Fast X-ray detectors based on bulk β -Ga₂O₃ (Fe)," J. Mater. Sci. 55, 9461-9469, 2020.

- Highly stable XRIC even at very low operating voltages (5,-5,0 V)
- Small exponential decay within the first minute that stabilizes after that
 - $\tau_1 = 57.7 \ sec$ and $\tau_2 > 10^6 \ sec$, stability
 - Less than 10% decrease in the first minute
- Operation status independent (for the ON/OFF frequency used)
 - Indicating ion migration and charge accumulation
 - Slight polarization effect



I. Hany et al., "Fast X-ray detectors based on bulk β -Ga₂O₃ (Fe)," J. Mater. Sci. 55, 9461-9469, 2020.

- a-Ga₂O₃: (H. Liang et al., "Flexible X-ray Detectors Based on Amorphous Ga₂O₃ Thin Films," ACS Photonics, vol. 6, no. 2, pp. 351–359, 2019.)
- Unintentionally doped β-Ga₂O₃: (X. Lu et al., "Schottky x-ray detectors based on a bulk β-Ga₂O₃ substrate," Appl. Phys. Lett., vol. 112, no. 10, p. 103502, 2018.) and (X. Lu et al., "X-ray Detection Performance of Vertical Schottky Photodiodes Based on a Bulk β-Ga₂O₃ Substrate Grown by an EFG Method," ECS J. Solid State Sci. Technol., vol. 8, no. 7, pp. Q3046–Q3049, 2019.)

Material	Preparation method	Rise time (s)	Decay time (s)	SNR
a-Ga ₂ O ₃	RF sputtering (PO ₂ 1.4×10^{-3} Pa)	15.5	1.1	-
	$\begin{array}{c} \text{RF Sputtering} \\ \text{(PO}_2 \ 1.0 \ \times \ 10^{-3} \\ \text{Pa)} \end{array}$	50.1	3.3	>10 ⁴
Unintentionally	EFG	18.3	20.9	>800
doped β-Ga ₂ O ₃		(-15 V)	(-15 V)	(-15 V)
		< 0.02	< 0.02	-
		(0 V)	(0 V)	
β-Ga ₂ O ₃ (Fe)	EFG	<0.3	<0.3	$\frac{>10^{3} (low voltages)}{>10^{2} (0 V and high voltage)}$

I. Hany et al., "Fast X-ray detectors based on bulk β -Ga₂O₃ (Fe)," J. Mater. Sci. 55, 9461-9469, 2020.



V. Temperature-dependent CL β-Ga₂O₃ (Fe)



- HT air annealing potentially decreases V_o concentration and eliminates V_{Ga}+V_o complexes.
 - Potential change in V_{Ga} nature and/or concentration.
- Red luminescence possible origins are (1) Nitrogen diffusion and (2) Cr impurities. New evidence points to the latter.

Defect	Defect type	Signature	
V _{Ga} +V _O	Vacancy	B ₁₋₄ (acceptor)	
Vo	Vacancy	B₅ and UV ₁₋₃ (donor)	
V _{Ga}	Vacancy	B ₅ (acceptor)	
Fe _{Ga}	Substitutional (dopant)	UV ₁ (acceptor)	
STH	Electronic defect	UV ₂₋₄	



I. Hany et al., "Low temperature cathodoluminescence study of Fe-doped β-Ga₂O₃," Materials Letters 257, 126744, 2019.

VI. Summary

- β-Ga₂O₃ (Fe) was investigated as a direct X-ray detection material motivated by its high resistivity and ultra-low leakage current.
 - High SNR under three operation modes
 - High linearity between X-ray induced photocurrent and X-ray tube current
 - Improved transport properties
 - Controlling Fe and Cr distribution may increase µт-factor
 - High stability upon continuous illumination for 15 minutes.
 - V_O and V_{Ga} potentially assist in the initial polarization effect
- The results demonstrate the great potential of β-Ga₂O₃(Fe) as a radiation resistant X-ray detector with excellent temporal response for a wide range of applications.

Thank you for your attention!

